## Editor's Comment:

Recommendation: Major revisions

Comments:

The manuscript entitles "Composition and Frequency dependent Dielectric properties of Cr-Co Nano ferrites" is written well and shows novelity, However there are some comments on this manuscript which needs to be justify before publication.

- 1. Results and Discussion parts needs to improve, what kind of hopping observed by AC Conductivity measurements? Is AC conductivity can be explained on the basis of Maxwell Wagner model for dielectric? If so then discussion part is not well written.
- 2. Introduction required more recent references, modification and also table for comparison with other ferrites composites and how it is better?
- 3. Please include SEM image of the sintered film.
- 4. The author did 900 °C air sintering. Is there any reason to choose 900C? Have you ever tried to anneal in different temperature? It would be good to show the XRD plot before and after 900 °C if the crystallization is the main reason for the sintering.
- 5. As per the Ref [16], authors have studied the effect of Cr<sup>3+</sup> ion on the structural and magnetic properties of the Co-ferrite nanoparticles. However, most of results for this material reported in this ref. [16] then what is the point to show electrical properties in this manuscript? It looks data is not sufficient for the work.
- Temperature is important parameters and it affect dielectric properties, temperature dependence dielectric constant and dissipation factor study is missing. Please add that data and cite some relevant references: Physica B 510 (2017) 74–79, Phys. Chem. Chem. Phys., 2017, 19, 210-218, IEEE Transactions on Dielectrics and Electrical Insulation Vol. 19, No. 1; February 2012, J. Phys. Chem. C, 2016, 120 (10), pp 5682–5693.
- 7. Please include error bar in Fig. 5
- 8. Introduction starts with Ferrites, what is the advantage of ferrites over piezoelectric and ferroelectric materials? Introduction needs modification.

## Editor's Details:

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